

IPM573 IP in R&D and Innovation

Level: 5

Credit Units: 5 Credit Units

Language: ENGLISH

Presentation Pattern: EVERY JULY

Synopsis:

IPM573 IP in R&D and Innovation delves into how R&D and intellectual property (IP) play complementary roles in technological innovation and the development of new products. The course explores this from an R&D perspective by assessing the different types of R&D models employed today and identifies IP issues related to R&D. Students will also learn how to determine subsequent steps needed based on issues identified and how to oversee implementation of any strategies.

Topics:

- Importance of R&D
- Objectives of IP and R&D in Innovation
- Types of R&D Models (1)
- Types of R&D Models (2)
- IP Issues Related to R&D (1)
- IP Issues Related to R&D (2)
- IP Issues Related to R&D (3)
- Types of Approaches to Deal with IP Issues
- Implement Suitable Approaches to R&D
- Monitor Implementation of Suitable Approaches to R&D
- Relevant Stakeholders
- Critical Success Factors Dealing with IP Issues in R&D

Learning Outcome:

- Contrast the various types of R&D models
- Appraise IP issues related to R&D
- Analyse objectives of approaches in addressing IP issues related to R&D
- Examine the different types of contractual agreements pertaining to R&D models
- Evaluate considerations when choosing types of approaches to deal with IP issues
- Assess critical success factors to deal with IP issues
- Evaluate different types of R&D models to identify IP issues related to R&D
- Analyse IP issues related to R&D to identify suitable approaches to address them
- Determine next steps to implement planned approaches
- Plan and oversee execution of approaches

Assessment Strategies - Regular Semester (Evening Class):

Components	Description	Weightage Allocation (%)
Overall Continuous Assessment	PRE-COURSE QUIZ 1	4

Overall Continuous Assessment	PRE-CLASS QUIZ 1	4
	PRE-CLASS QUIZ 2	2
	PARTICIPATION 1	5
	GROUP BASED ASSIGNMENT 1	45
Overall Examinable Components	Written Exam	40
Total		100

*The information listed is subject to review and change.